Fig. 1A formation of base insulating film/ formation of semiconductor film

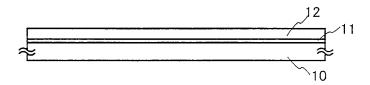


Fig. 1B laser anneal

Fig. 1C heat treatment process

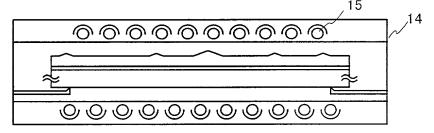


Fig. 1D formation of semiconductor film

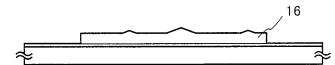


Fig. 2A formation of base insulating film/ formation of semiconductor film

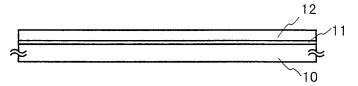


Fig. 2B laser anneal

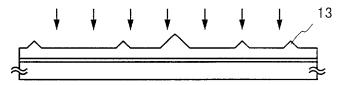


Fig. 2C formation of semiconductor film

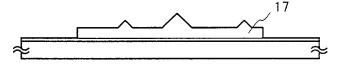


Fig. 2D heat treatment process



Fig. 3A formation of base insulating film/ formation of semiconductor film

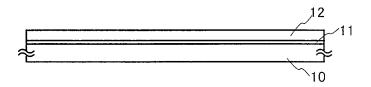


Fig. 3B irradiation of strong light

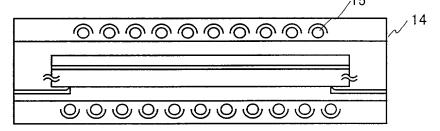


Fig. 3C laser anneal

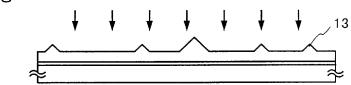


Fig. 3D heat treatment process

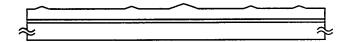


Fig. 3E formation of semiconductor film

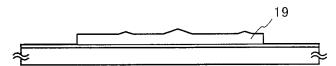


Fig. 4A formation of conductive film/formation of insulating film /formation of semiconductor film

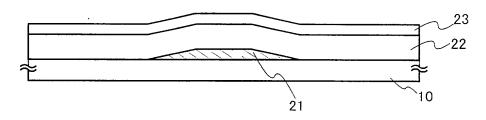


Fig. 4B laser anneal

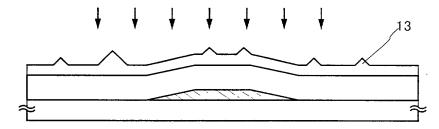


Fig. 4C heat treatment process

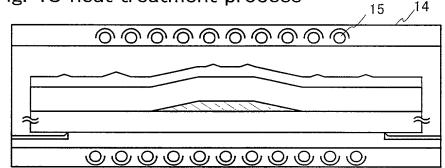
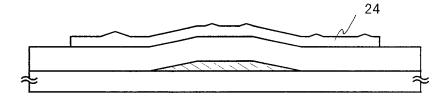
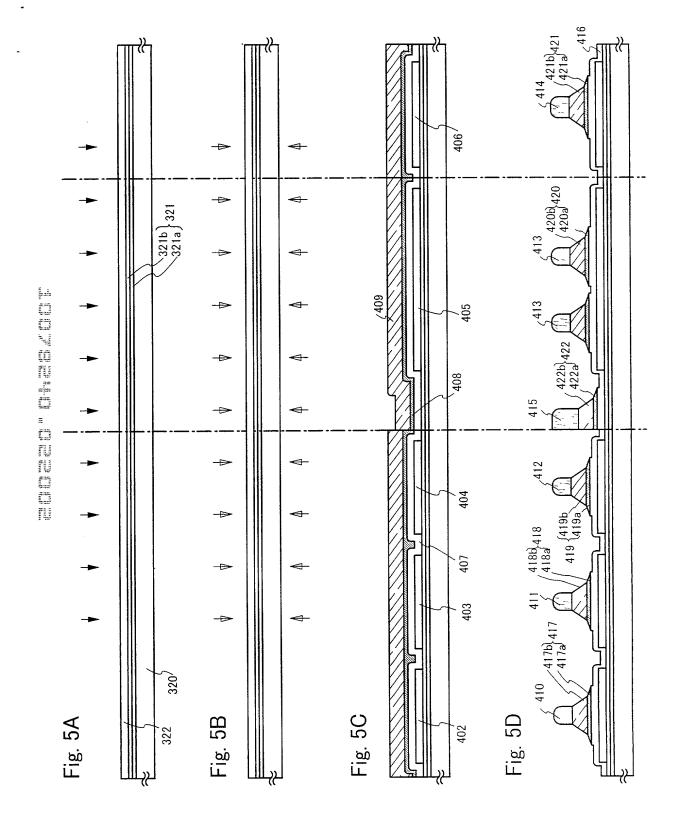
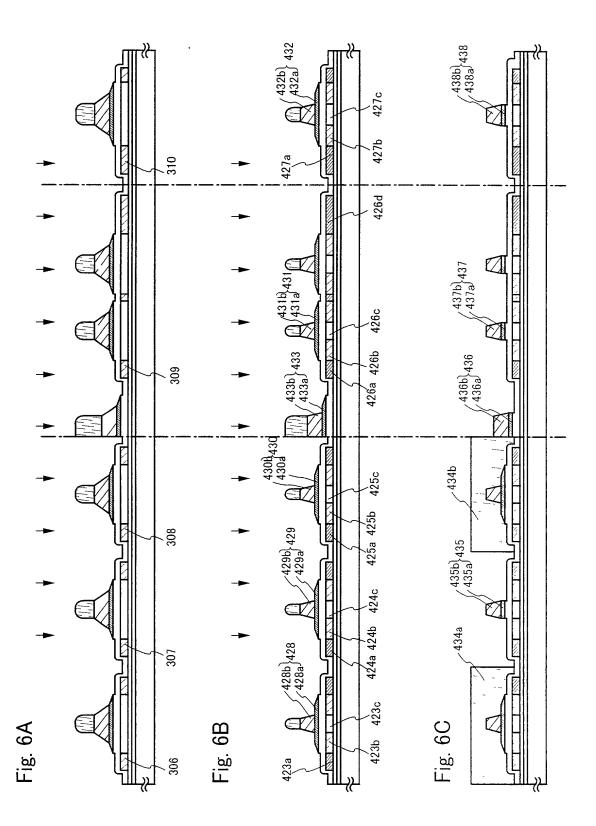


Fig. 4D formation of semiconductor film







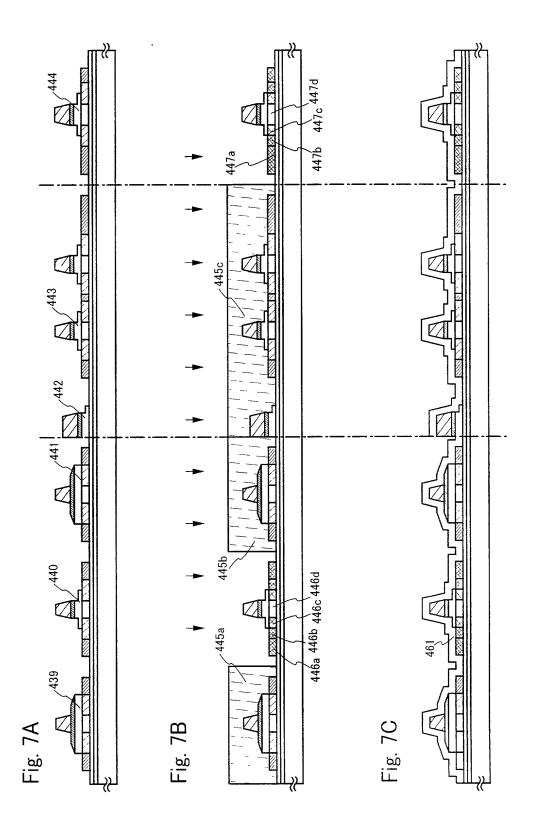


Fig. 8

formation of second interlayer insulating film/formation of pixel electrode and wirings

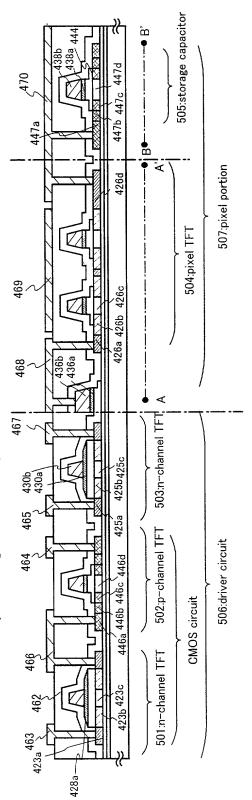


Fig. 9

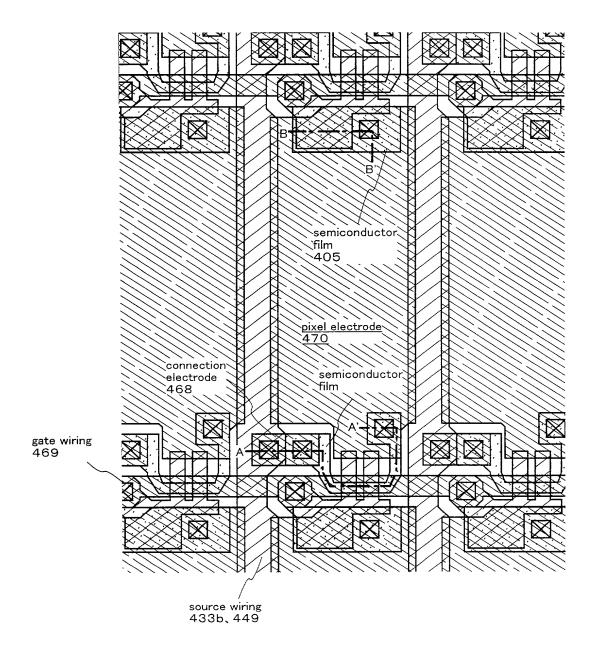


Fig. 10

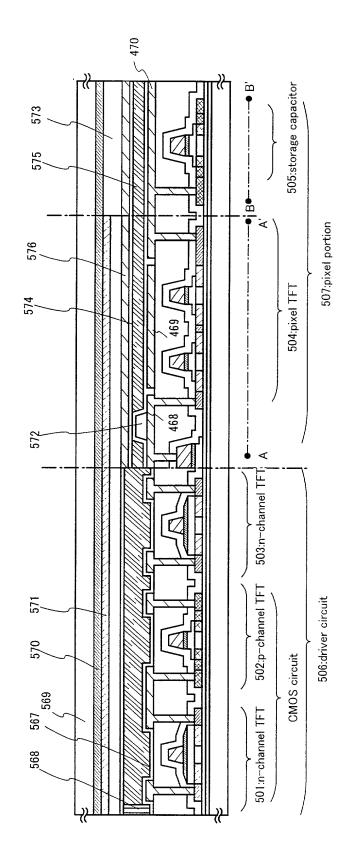


Fig. 11

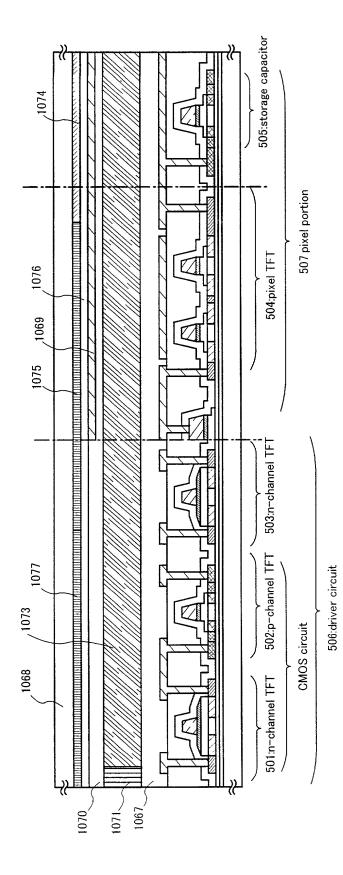


Fig. 12

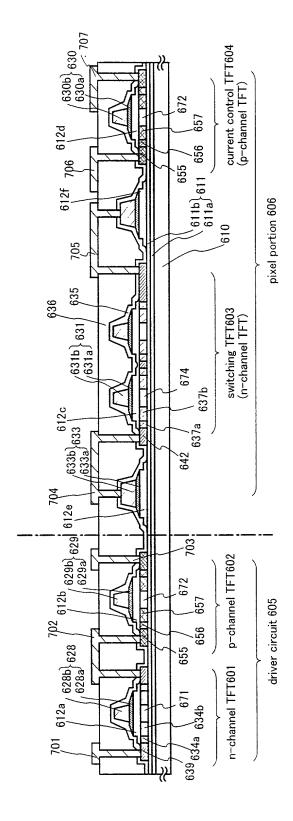
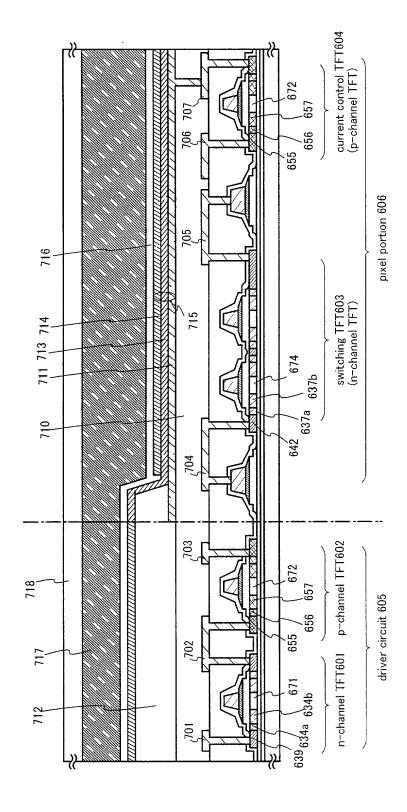


Fig. 13



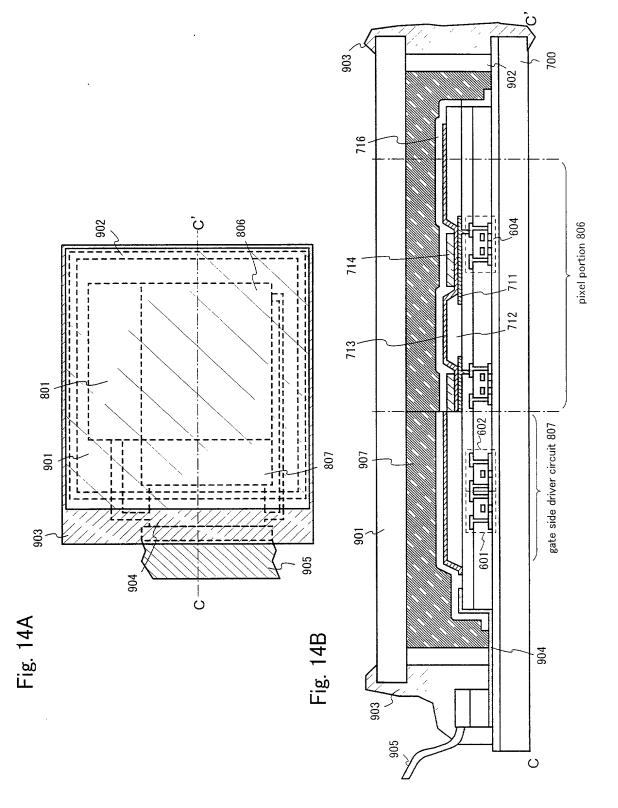
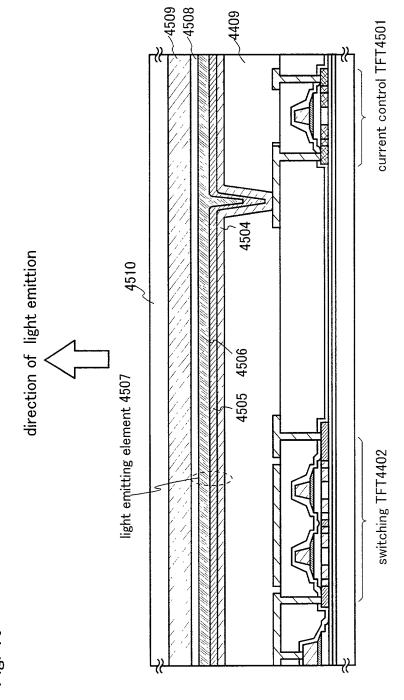
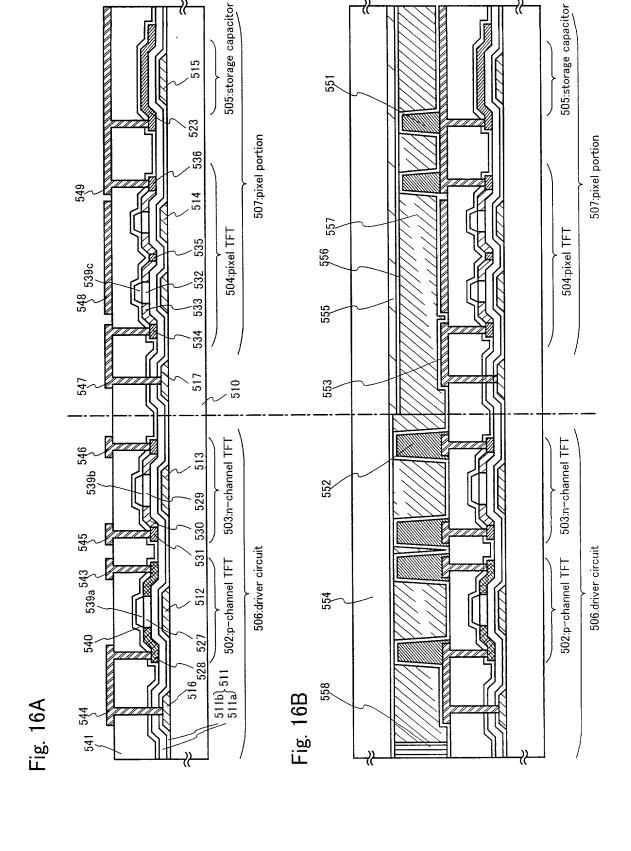
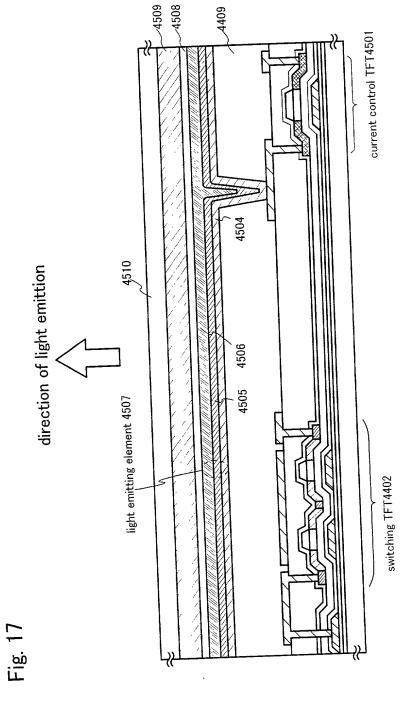
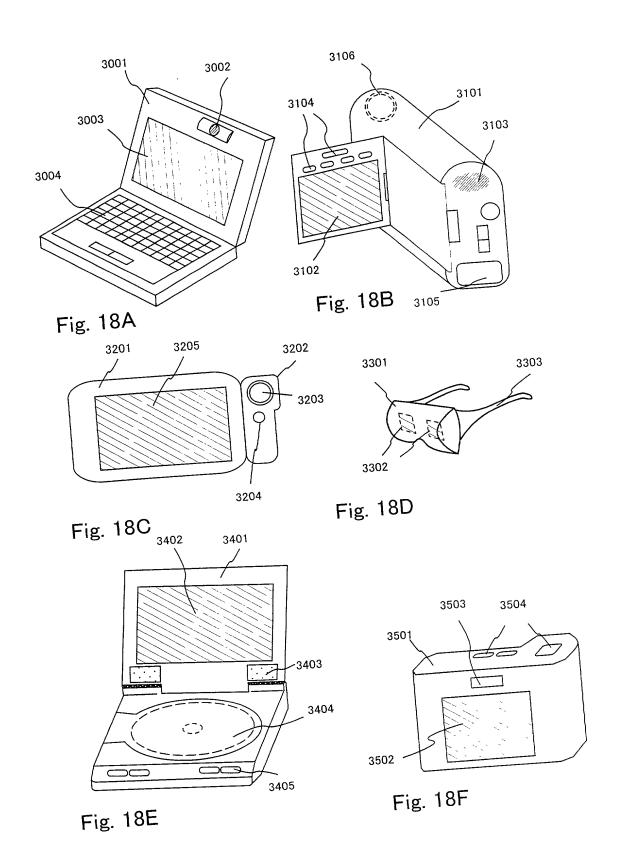


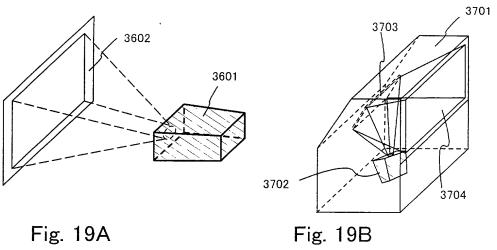
Fig. 15











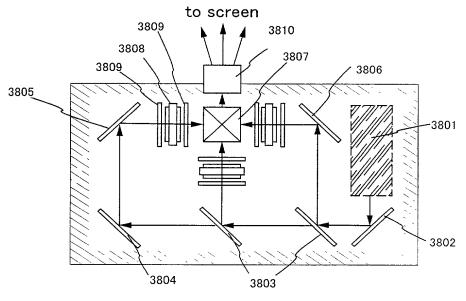


Fig. 19C

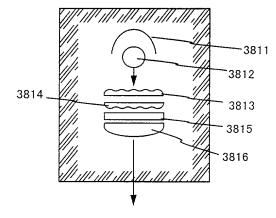


Fig. 19D

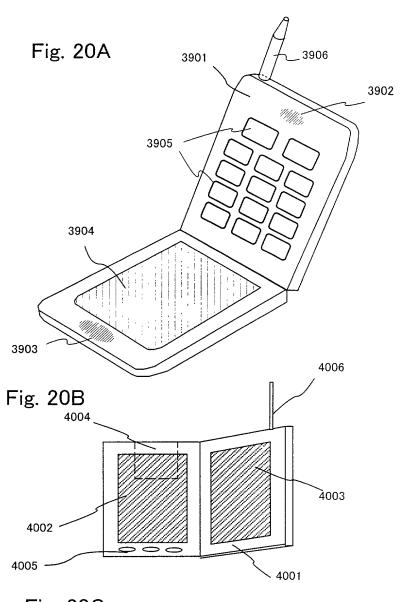


Fig. 20C

4101

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4103